中文摘要
英文摘要
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符號說明

A: 1.54×10⁻¹⁰ (A V⁻² eV) B: 6.83×10^9 (V eV^{-3/2} m⁻¹) d: distance between cathode and anode d₁: the distance of emitters e: electron charge E: applied electric field E_{to}: turn-on electric field E_f: Fermi-level E_{Fo}: Fermi-level at 0K E_{vac}: energy level in the vacuum h: effective barrier height h₁: the height of emitters I: field emission current J: field-emission current density L: length q: electron charge r: root diameter S: slope of the F-N plot S_F: field-screening factor t: time T: temperature V: applied voltage W_a: surface potential barrier y: 3.7947×10⁻⁴E^{1/2}/φ α : emitting area

 β : local field enhancement factor at the emitting surface

 ε_0 : permittivity of free space

φ: work function

 $\Delta \varphi$: decrease in barrier height

ρ: density



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